## **CLAIMS**

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1. A method of fabricating an active matrix display comprising:

forming a silicon layer over an insulating layer and a supporting substrate;

forming an array of transistors with the silicon layer to form an active matrix circuit on the supporting substrate;

forming an array of pixel electrodes with a polycrystalline silicon material; and

transferring the array of transistors and the array of pixel electrodes to a second substrate.

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- 2. The method of Claim 1 further comprising forming interconnects between the transistors and the pixel electrodes.
- 3. The method of Claim 1 further comprising positioning a light shield between the transistors and the second substrate.
  - 4. The method of Claim 1 wherein the second substrate comprises an optically-transmissive substrate.
- 5. The method of Claim 4 further comprising positioning a material between the array of pixel electrodes and a counterelectrode, such that selective actuation of a pixel electrode produces an electric field across a portion of the material disposed between the pixel electrode and the counterlectrode, thereby producing a change in a light transmission property of the material.

6. The method of Claim 5, wherein the material positioned between the array of pixel electrodes and the counterelectrode comprises a liquid crystal material.

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